

Abstract:

The present invention relates to an illumination system for microlithography,
5 especially for wavelengths ≤ 193 nm, especially preferably for EUV lithography for
illuminating a field in a field plane with at least one optical integrator which splits
up a light bundle emitted by a light source into a plurality of light channels each
having a light intensity,
characterized in that
10 a filter is provided in the light path from the light source to the field plane, with the
filter comprising filter elements which are configured in such a way that the light
intensity of at least one light channel is reduced in the light path after the filter
element.

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